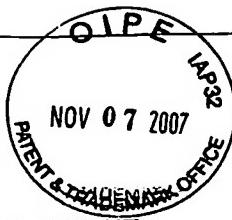


FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: November 7, 2007

Page **1** of **4**

Atty. Dkt. No.	M#	Client Ref.
081468	0309196	P-1851.000-US
Applicant: Aleksey Yurievich KOLESNYCHENKO, et al.		
Appln. No.: 10/823,777		
Filing Date: April 14, 2004		
Examiner: GUTIERREZ, Kevin C. Group Art Unit: 2851		

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
/AM/	AR	2003/0030916 A1	02/2003	Suenaga			
	BR	2004/0118184 A1	06/2004	Violette			
	CR	2004/0169834 A1	09/2004	Richter et al.			
	DR	2004/0169924 A1	09/2004	Flagello et al.			
	ER	2004/0180294 A1	09/2004	Baba-Ali et al.			
	FR	2004/0180299 A1	09/2004	Rolland et al.			
	GR	2004/0114117 A1	06/2004	Bleeker			
	HR	2004/0160582 A1	08/2004	Lof et al.			
	IR	2004/0165159 A1	08/2004	Lof et al.			
	JR	2004/0207824 A1	10/2004	Lof et al.			
	KR	2004/0211920 A1	10/2004	Derkzen et al.			
	LR	2004/0224265 A1	11/2004	Endo et al.			
	MR	2004/0224525 A1	11/2004	Endo et al.			
	NR	2004/0227923 A1	11/2004	Flagello et al.			
	OR	2004/0253547 A1	12/2004	Endo et al.			
	PR	2004/0253548 A1	12/2004	Endo et al.			
	QR	2004/0257544 A1	12/2004	Vogel et al.			
	RR	2004/0259008 A1	12/2004	Endo et al.			
	SR	2004/0259040 A1	12/2004	Endo et al.			
↓	TR	2004/0263808 A1	12/2004	Sewell			
	UR	2006/0023182	02/2006	Novak et al.			
/AM/	VR	2006/0238730	10/2006	Nei et al.			

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
/AM/	WR	EP 0 834 773 A2	04/1998	Europe	Suwa				
	XR	JP A 57-153433	09/1982	Japan	Takanashi et al.		X		
↓	YR	JP A 59-19912	02/1984	Japan	Kawamura et al.		X		
	ZR	JP A 05-62877	03/1993	Japan	Shinohara		X		
/AM/	AAR	JP A 08-316125	11/1996	Japan	Rudorfu et al.		X		

Examiner /Alan Mathews/ Date Considered: 01/20/2008

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office		Atty. Okt. No.	M#	Client Ref.
		081468	0309196	P-1851.000-US
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant: Aleksey Yurievich KOLESNYCHENKO, et al.		
		Appln. No.: 10/823,777		
		Filing Date: April 14, 2004		
Date: November 7, 2007		Page 2 of 4	Examiner: GUTIERREZ, Kevin C. Group Art Unit: 2851	

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
/AM/	BBR	2005/0030506 A1	02/2005	Schuster			
	CCR	2005/0036121 A1	02/2005	Hoogendam			
	DDR	2005/0036183 A1	02/2005	Yeo et al.			
	EER	2005/0036184 A1	02/2005	Yeo et al.			
	FFR	2005/0036213 A1	02/2005	Mann et al.			
	GGR	2005/0037269 A1	02/2005	Levinson			
	HHR	2005/0046934 A1	03/2005	Ho et al.			
	IIR	2005/0048223 A1	03/2005	Pawloski et al.			
	JJR	2005/0068639 A1	03/2005	Pierrat et al.			
	KKR	2005/0073670 A1	04/2005	Carroll			
	LLR	2005/0084794 A1	04/2005	Meagley et al.			
	MMR	2005/0094116 A1	05/2005	Flagello et al.			
	NNR	2005/0100745 A1	05/2005	Lin et al.			
	OOR	2005/0110973 A1	05/2005	Streefkerk et al.			
	PPR	2005/0117224 A1	06/2005	Shafer et al.			
	QQR	2005/0122497 A1	06/2005	Lyons et al.			
	RRR	2005/0134815 A1	06/2005	Van Santen et al.			
	SSR	2005/0141098 A1	06/2005	Schuster			
	TTR	2005/0190455 A1	09/2005	Rostalski et al.			
	UUR	2005/0217135 A1	10/2005	O'Donnell et al.			
↓	VVR	2005/0217137 A1	10/2005	Smith et al.			
	WWR	2005/0217703 A1	10/2005	O'Donnell			
/AM/	XXR	6,952,253	10/2005	Lof et al.			

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	YYR								
	ZZR								
	AAAR								

Examiner /Alan Mathews/ Date Considered: 01/20/2008

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
081468	0309196	P-1851.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Aleksey Yurievich KOLESNYCHENKO, et al.

Appn. No.: 10/823,777

Filing Date: April 14, 2004

Date: November 7, 2007 Page 3 Of 4 Examiner: GUTIERREZ, Kevin C. Group Art Unit: 2851

FOREIGN PATENT DOCUMENTS						English Abstract		Translation Readily Available		
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclose	No
/AM/	BBBBR	WO 2002/091078 A1	11/2002	PCT	Switkes et al.		X			
	CCCR	WO 2004/077154 A1	09/2004	PCT	Babi-Ali et al.		X			
	DDDR	WO 2004/081666 A1	09/2004	PCT	Rolland et al.		X			
	EEER	WO 2004/090577 A2	10/2004	PCT	Binnard		X			
	FFFR	WO 2004/090633 A2	10/2004	PCT	Eaton		X			
	GGGR	WO 2004/090634 A2	10/2004	PCT	Hazelton et al.					
	HHHR	WO 2004/092833 A2	10/2004	PCT	Novak et al.		X			
	IIIR	WO 2004/093130 A2	10/2004	PCT	Hazelton et al.		X			
	JJJR	WO 2004/093159 A2	10/2004	WIPO						
	KKKR	WO 2004/092830 A2	10/2004	WIPO						
	LLLR	WO 2004/095135 A2	11/2004	PCT	Novak					
	MMMR	WO 2005/001432 A2	01/2005	PCT	Kunz et al.		X			
	NNNR	WO 2005/003864 A2	01/2005	PCT	Hemker et al.		X			
	OOOR	WO 2005/006026 A2	01/2005	PCT	Sogard		X			
	PPPR	WO 2005/008339 A2	01/2005	PCT	Van der net et al.		X			
	QQQR	WO 2005/013008 A2	02/2005	PCT	Levinson		X			
	RRRR	WO 2005/015283 A1	02/2005	PCT	Mann et al.		X			
	SSSR	WO 2005/017625 A2	02/2005	PCT	Levinson		X			
	TTTR	WO 2005/022266 A2	03/2005	PCT	Pawloski et al.		X			
	UUUR	WO 2005/024325 A2	03/2005	PCT	Ho et al.		X			
	VVVR	WO 2005/024517 A2	03/2005	PCT	Poon et al.		X			
	WWWR	WO 2005/034174 A2	04/2005	PCT	Caroll		X			
	XXXR	WO 2005/054953 A2	06/2005	PCT	Gellrich et al.		X			
	YYYR	WO 2005/054955 A2	06/2005	PCT	Streefkerk et al.		X			
	ZZZR	WO 2005/062128 A2	07/2005	PCT	Lyons et al.		X			
	AAAAR	JP A 10-116760	05/1998	Japan	Ebihara		X			
	BBBBR	JP A 11-166990	06/1999	Japan	Hagiwara		X			
↓	CCCCR	JP A 06-181157	06/1994	Japan	Umeda et al.		X			
	DDDR	JP A 05-304072	11/1993	Japan	Yanagisawa		X			
/AM/	EEEER	WO 2005/019935 A2	03/2005	WIPO	Phan et al.					

Examiner /Alan Mathews/ Date Considered: 01/20/2008

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office		Atty. Dkt. No.	M#	Client Ref.
		081468	0309196	P-1851.000-US
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant: Aleksey Yurievich KOLESNYCHENKO, et al.		
		Appln. No.: 10/823,777		
		Filing Date: April 14, 2004		
Date: November 7, 2007		Page 4 of 4	Examiner: GUTIERREZ, Kevin C. Group Art Unit: 2851	

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
FFFFR						
GGGGR						
HHHHR						
IIIR						
JJJJR						
KKKKR						
LLLLR						
MMMR						
NNNR						
OOOR						
PPPR						

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
	QQQQR							
	RRRRR							
	SSSSR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

/AM/ TTTTR	Emerging Lithographic Technologies VI, Proceedings of SPIE, vol. 4688 (2002), "Semiconductor Foundry, Lithography, and Partners", B.J. Lin, pages 11-24.						
/AM/ UUUUR	Optical Microlithography XV, Proceedings of SPIE, vol. 4691 (2002), "Resolution Enhancement of 157 nm Lithography by Liquid Immersion", M. Switkes et al., pages 459-465.						
/AM/ VVVVR	J. Microlith., Microfab., Microsyst., vol. 1 No. 3, October 2002, Society of Photo-Optical Instrumentation Engineers, "Resolution enhancement of 157 nm lithography by liquid immersion", M. Switkes et al., pages 1-4.						
/AM/ WWWWWR	Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (2003), "Immersion lithography; its potential performance and issues", Soichi OWA et al., pages 724-733.						
/AM/ XXXXR	Information Disclosure Statement dated Oct. 19, 2006 for US Application No. 11/473,147						
/AM/ YYYYR	Non-Final Office Action, dated Mar. 20, 2007, issued for US Application No. 11/473,147						

Examiner /Alan Mathews/ Date Considered: 01/20/2008

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.